METHOD OF PRODUCING COATINGS ON ELECTRONIC SUBSTRATES

ABSTRACT

This invention pertains to a method for producing an insoluble coating on a substrate by curing a composition comprising hydrogen silsesquioxane at a temperature of 375°C. or less for a time sufficient to produce a coating having >80% SiH. It has been found that when said resin is thus cured the insoluble SiH containing coating has improved film stress.